

BIS(AMINOPHENOL) DERIVATIVE, PROCESS FOR PRODUCING THE SAME, POLYAMIDE RESIN, POSITIVE PHOTSENSITIVE RESIN COMPOSITIONS, PROTECTIVE FILM, INTERLAYER DIELECTRIC, SEMICONDUCTOR DEVICE, AND DISPLAY ELEMENT

ABSTRACT

A bis(aminophenol) derivative having substituents at positions adjacent to two amino groups is provided. The bis(aminophenol) derivative is used as a raw material
5 of a polyamide resin for a positive-tone photosensitive resin composition. A polyamide resin comprising bis(aminophenol) and a structure derived from a carboxylic acid is also provided, the bis(aminophenol) having substituents at positions adjacent to the two amino groups. A positive-tone photosensitive resin composition comprising a polybenzooxazole precursor resin, exhibiting high sensitivity and a high cyclization rate
10 even when cured at a low temperature is provided. Also provided is a positive-tone photosensitive resin composition comprising a polyamide resin having an imide structure, an imide precursor structure, or an amide acid ester structure. The composition exhibits high sensitivity and produces a cured product having low water absorption even when cured at a low temperature.

No Figure